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Stationary source emissions — Determination of greenhouse gas emissions in energy-intensive industries — Part 7: Semiconductor and display industries

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# iTeh Standards (https://standards.iteh.ai) Document Preview

ISO/FDIS 19694-7

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#### Foreword

ISO (the International Organization for Standardization) is a worldwide federation of national standards bodies (ISO member bodies). The work of preparing International Standards is normally carried out through ISO technical committees. Each member body interested in a subject for which a technical committee has been established has the right to be represented on that committee. International organizations, governmental and non-governmental, in liaison with ISO, also take part in the work. ISO collaborates closely with the International Electrotechnical Commission (IEC) on all matters of electrotechnical standardization.

The procedures used to develop this document and those intended for its further maintenance are described in the ISO/IEC Directives, Part 1. In particular, the different approval criteria needed for the different types of ISO documents should be noted. This document was drafted in accordance with the editorial rules of the ISO/IEC Directives, Part 2 (see <a href="https://www.iso.org/directives">www.iso.org/directives</a>).

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For an explanation of the voluntary nature of standards, the meaning of ISO specific terms and expressions related to conformity assessment, as well as information about ISO's adherence to the World Trade Organization (WTO) principles in the Technical Barriers to Trade (TBT), see <a href="https://www.iso.org/iso/foreword.html">www.iso.org/iso/foreword.html</a>.

This document was prepared by Technical Committee ISO/TC 146, Air quality, Subcommittee SC 1, Stationary source emissions.

A list of all parts in the ISO 19694 series can be found on the ISO website.

Any feedback or questions on this document should be directed to the user's national standards body. A complete listing of these bodies can be found at <a href="https://www.iso.org/members.html">www.iso.org/members.html</a>.

### Introduction

#### 0.1 General

This document for the semiconductor and display industry has been based on the Chapter 6, Volume 3, IPCC Methodology Report: "2019 Refinement to the 2006 IPCC Guideline for National Greenhouse Gas Inventories (2019 Refinement)".

This document is harmonized with ISO 14064-1 and 19694-1. As this document, which deals with specific sectors, that is, requirements for the semiconductor and display industry, for has been harmonized with ISO 14064-1 and ISO 19694-1, which deal with broader requirements, see also, ISO 14064-1 and 19694-1. These standards and this document provide a harmonized method for:

- \_\_measuring, testing and quantifying methods for GHGsgreenhouse gas (GHG) emissions;
- assessing the level of GHG emissions performance of production processes over time, at production sites; and the establishment and provision of reliable, accurate and quality information for reporting and verification purposes.

GHG emissions offset mechanisms, including but not limited to voluntary offset schemes or nationally or internationally recognized offset mechanisms, shall not be used at any point in the GHG assessment according to this document.

 establishing and providing reliable, accurate and quality information for reporting and verification purposes.

### 0.2 Overview of semiconductor and display manufacturing process

Semiconductor and display manufacture include processes, such as thin film deposition (TFD) or plasma etching and water cleaning (EWC) of silicon-containing materials, that results result in significant carbon dioxide emissions. These emissions are the results of the fluorinated compounds (FC) gases and nitrous oxide  $\{N_2O\}$  used in the manufacturing process. Other greenhouse gas (GHG) emissions in semiconductor and display industry include the  $CO_2$  and  $CH_4$  from direct emissions of combustion, transportation, manufacturing process or indirect emissions (e.g., room heating, on-site transports, on-site power generation, external power production and external transports).

FC gases are used in two important steps of electronics manufacturing: (i) 89-8713-4b76-9e68-c75e91083b6e/iso-fdis-19694-7

- a) plasma etching and wafer cleaning (EWC) of silicon-containing materials, and (ii)
- <u>b)</u> cleaning of the chamber walls of thin-film deposition (TFD) and diffusion tools after processing substrates.

The semiconductor and display industry manufactures use  $N_2O$  as an input gas duringin TFD processes, and forin other  $N_2O$  using manufacturing processes that use  $N_2O$ , such as diffusion and dry removal of photoresist.

The process emission of FC gases and N<sub>2</sub>O should be estimated following Chapter 6, Volume 3, IPCC Methodology Report "using the 2019 Refinement to the 2006 IPCC Guideline for National Greenhouse Gas Inventories. In this document, references are made to the relevant parts of 2019 Refinement to the 2006 IPCC Guideline for National Greenhouse Gas Inventories (2019 Refinement)", which is annexed to this document. In this document, instructions are given as to which part of the 2019 Refinement should be depending on the element used for each element which companies need to consider so that they can find in the Annex relevant appropriate guidance including equationsthat includes formulae, tables, etc. It should be noted. However, the 2019 Refinement may be subject to correction the 2006 IPCC Guideline for National Greenhouse Gas Inventories can be corrected if some errors are detected. Therefore, companies are strongly encouraged to keep referring to Reference [64] and to replace the Annex B with the latest

corrected version of Chapter 6, Volume 3 of the 2019 Refinement to the 2006 IPCC Guideline for National Greenhouse Gas Inventories when it is made available.

Other CO<sub>2</sub> sources include direct GHG emissions from fuel combustion (e.g., room heating and cooling on site vehicles and on site power generation), and indirect GHG emissions from imported power consumed by the organization (e.g., external electricity, heat, or steam generation and transported).

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Stationary source emissions — Determination of greenhouse gas emissions in energy-intensive industries — Part 7: Semiconductor and display industries

# 1 Scope

This document provides a methodology for calculating greenhouse gas (GHG) emissions from the semiconductor and display industry. Lethis document includes the manufacture of semiconductor devices, microelectromechanical systems (MEMS), photovoltaic (PV) devices, and displays. This document allows for the reporting of to report GHG emissions for various purposes and on different bases, such as a per-plant basis, per-company basis (by country or by region), or on an international group basis. This document addresses all of the following direct and indirect sources of GHG as defined in ISO 14064-1:

- direct GHG emissions (<u>[as defined in ISO 14064-1:2018, 5.2.4 a}</u>)] from sources that are owned or controlled by the company, such as emissions resulting from the following sources:
  - process: fluorinated compound (FC) gases and nitrous oxide (N<sub>2</sub>O) used in EWG, RPG, IPG, ITG, N<sub>2</sub>O TFD, etching and wafer cleaning (EWC), remote plasma cleaning (RPC), in situ plasma cleaning (IPC), in situ thermal cleaning (ITC), N<sub>2</sub>O thin film deposition (TFD), and other N<sub>2</sub>O using process;
  - fuel combustion related to equipment and on-site vehicles, room heating/cooling;
  - fuel combustion of fuels for on-site power generation;
- indirect GHG emissions { [as defined in ISO 14064-1:2018, 5.2.4 b]] from the generation of imported electricity, heat or steam consumed by the organization;

—Other indirect GHG emissions <u>{[as defined in ISO 14064-1:2018, 5.2.4 c-] to f],]]</u>, which are the consequence of an organization's activities, but arise from GHG sources that are owned or controlled by other organizations, are excluded from this document.

# 2 Normative references

The following documents are referred to in the text in such a way that some or all of their content constitutes requirements of this document. For dated references, only the edition cited applies. For undated references, the latest edition of the referenced document (including any amendments) applies.

ISO/IEC Guide 98-3:2008, Uncertainty of measurement — Part 3: Guide to the expression of uncertainty in measurement (GUM:1995)

ISO 19694—1:2021, Stationary source emissions — Determination of greenhouse gas emissions in energyintensive industries — Part 1: General aspects

ISO 14064–1:2018, Greenhouse gases — Part 1: Specification with guidance at the organization level for quantification and reporting of greenhouse gas emissions and removals

ISO/IEC Guide 98-3:2008, Uncertainty of measurement — Part 3: Guide to the expression of uncertainty in measurement (GUM:1995)

<u>Calvo Buendia, E., Tanabe, K., Kranjc, A., Baasansuren, J., Fukuda, M., Ngarize, S., Osako, A., Pyrozhenko, Y., Shermanau, P. and Federici, S.</u> 2019 Refinement to the 2006 IPCC Guideline for National Greenhouse Gas Inventories (2019 Refinement), Volume 3, Chapter 6 Electronics. <u>URL: https://www.ipccnggip.iges.or.jp/public/2019rf/index.html</u>

#### 3 Terms and definitions

For the purposes of this document, the terms and definitions given in ISO 19694-1: $\frac{2021}{2000}$  and the following apply.

ISO and IEC maintain terminology databases for use in standardization at the following addresses:

- ISO Online browsing platform: available at <a href="https://www.iso.org/obp">https://www.iso.org/obp</a>
- IEC Electropedia: available at https://www.electropedia.org/

#### 3.1

#### base year

specific, historical period identified for the purpose of comparing <u>CHG greenhouse gas</u> emissions (3.<u>1814</u>) or <u>greenhouse gas (3.13)</u> removals or other <u>CHG greenhouse gas-</u>related information over time

Note 1 to entry: Base year emissions or removals may be quantified based on a specific period (e.g. a year or part of year where seasonality is a feature of the *organization's* (3.3527) activity) or averaged from several periods (e.g. several years).

[SOURCE: ISO 19694-1:2021, 3.3], modified — Note 1 to entry has been added.]

#### 3.2

# carbon dioxide equivalent

# $CO_2e$

unit for comparing the radiative forcing of a  $\frac{GHGgreenhouse\ gas}{2}$  (3.1613) to that of carbon dioxide

Note 1 to entry: The carbon dioxide equivalent is calculated using the mass of a given  $\frac{GHG}{(3.16)}$  greenhouse gas multiplied by its global warming potential (3.15).

[SOURCE: ISO 14064-1:2018, 3.1.13]

# 3.3

# chemical vapour deposition

#### CVD

process—(3.39) for manufacturing preforms by which vapours and gases react chemically to produce deposits at the surface of a substrate

### 3.4

# direct greenhouse gas emission direct GHG emission

emission from greenhouse gas sources (3.21) owned or controlled by the reporting organization (3.35)

Note 1 to entry: This document uses the concepts of equity share (3.6) or financial control, (3.10), or operational control to establish organizational boundaries (3.36).

[SOURCE: ISO 19694-1:2021, 3.8]

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tps://standards.iteh.ai)

#### 3.5

#### emission report

stand alone document intended to communicate an *organization's* (3.35) information related to *GH* (3.16) and energy, including the results of its performance assessment

[SOURCE: ISO 19694-1:2021, 3.9]

#### 3.6

# equity share

percentage of economic interest in, or benefit derived from, a facility (3.97)

Note 1 to entry: Under this approach, an *organization* (3.3527) (corporation, group) or a company consolidates its *GHGgreenhouse gas emissions* (3.18) in accordance with14) according to the (pro rata) equity share it holds in each operation, i.e. in accordance withaccording to ownership. As an exception, no emissions are consolidated for so-called fixed asset investments where a company owns only a small part of the total shares of an operation and exerts neither significant influence nor financial control (3.10); other possible exceptions relate to the economic substance of a relationship.

### 3.<del>7</del>5

# etching

removingremoval of surface material

Note 1 to entry: Etching can be applied usingwith liquids agents (wet chemical etching) or usingwith gases in a recipient (dry etching, plasma etching). The etching agent reacts chemically with the substrate.

[SOURCE: ISO 12679:2011, 3.3]

#### 3.8<u>6</u>

# etching and wafer cleaning

# **EWC**

removal process  $\frac{(3.39)}{(3.75)}$  of chemical and particle impurities without altering or damaging the wafe surface after *etching* (3.75) the surface material

#### 3.<mark>9</mark>7

# facility

single installation, set of installations or production processes (3.39) (stationary or mobile), which can be defined within a single geographical boundary, organizational unit or production process (3.39)

[SOURCE: ISO 14064-1:2018, 3.4.1]

# 3.<del>10</del>8

# financial control

the ability of an *organization* (3.35) to direct the financial and operating policies of an operation with view to gaining economic benefits from its activities.

Note 1 to entry: The financial control usually exists if the *organization* (3.35) has the right to the majority benefits of the operation, or if it retains the majority risks and rewards of ownership of the operation's assets. Under this approach, companies consolidate 100 % of the emissions of those operations over which they have financial contro; as an exception, consolidation according to *equity share* (3.6) is required for joint ventures where partners have joint financial control.

[SOURCE: ISO 19694-1:2021, 3.12]

# 3.11

fixed combustion emissionsemission

emissionsemission from the fixed combustion, including power generation, heat and electricity generation

#### 3.129

#### fluorinated compounds and N2O

### FCs and N<sub>2</sub>O

various types of fluorinated compounds and liquids use such as used to manufacture electrical products

EXAMPLE \_\_\_CF<sub>4</sub>, C<sub>2</sub>F<sub>6</sub>, C<sub>3</sub>F<sub>8</sub>, c-C<sub>4</sub>F<sub>8</sub>, C<sub>4</sub>F<sub>6</sub>, c-C<sub>5</sub>F<sub>8</sub>, CH<sub>3</sub>F, CH<sub>2</sub>F<sub>2</sub>, CHF<sub>3</sub>, C<sub>2</sub>HF<sub>5</sub>, NF<sub>3</sub>, SF<sub>6</sub>, COF<sub>2</sub>, F<sub>2</sub>, C<sub>4</sub>F<sub>8</sub>O and N<sub>2</sub>O for manufacturing electrical products.

#### 3.1310

#### fossil <del>carbon</del>fuel

carbon that is contained in fossilized material

Note 1 to entry: Examples of fossilized material are fuels from fossilized materials listed by the Intergovernmental Panel on Climate Change (IPCC)

EXAMPLE Coal, oil and natural gas and peat.

[SOURCE: ISO 14067:2018, 19694-3.1.7.:2023, 3.18]

#### 3.4411

#### fuel combustion

intentional oxidation of materials within an apparatus that is designed to provide heat or mechanical work to a process (3.39), or for useto be used away from the apparatus.

#### 3.<del>15</del>12

# global warming potential

GWP

index, based on radiative properties of <u>GHGsgreenhouse gases</u> (3.1613), measuring the radiative forcing following a pulse emission of a unit mass of a given <u>GHG (3.16)greenhouse gas</u> in the present-day atmosphere integrated over a chosen time horizon (e.g., 100 years), relative to that of carbon dioxide  $(CO_2)$ 

[SOURCE: ISO 14064-1:2018, 3.1.12], modified — "(e.g. 100 years)" has been added to the definition.]

#### 3.<del>16</del>13

# greenhouse gas

#### GHG

gaseous constituent of the atmosphere, both natural and anthropogenic, that absorbs and emits radiation at specific wavelengths within the spectrum of infrared radiation emitted by the Earth's surface, the atmosphere and clouds

Note 1 to entry: For list of greenhouse gases (3.16), see latest Intergovernmental Panel on Climate Change (IPCC) Assessment Report.

Note 2 to entry: Water vapour and ozone are anthropogenic as well as natural greenhouse gases  $\frac{(3.16)}{100}$  but are not included as recognized greenhouse gases  $\frac{(3.16)}{100}$  due to difficulties, in most cases, in isolating the human-induced component of global warming attributable to their presence in the atmosphere.

[SOURCE: ISO 14064-1:2018, 3.1.1]

# 3.<del>17</del>14

# greenhouse gas activity data

**GHG** activity data

activity data

quantitative measure of activity that results in greenhouse gas emission (3.18) or GHG (3.16) removal

[SOURCE: ISO 19694-1:2021, 3.16]

3.18

greenhouse gas emission

**GHG** emission

release of a GHGgreenhouse gas (3.16) to 13) into the atmosphere

[SOURCE: ISO 14064-1:2018, 3.1.25]

3.<del>19</del>15

greenhouse gas emission factor

**GHG** emission factor

coefficient relating *GHGgreenhouse gas* (3.13) activity data (3.17) with the *GHGgreenhouse gas* emission (3.1814)

[SOURCE: ISO 14064-1:2018, 3.1.7—, modified.— "GHG" has been removed from the second term and Note 1 to entry 4 has been deleted.]

3.2016

greenhouse gas inventory

**GHG** inventory

list of greenhouse gas sources (3.<del>21), GHG</del>17) and greenhouse gas (3.13) sinks, and their quantified greenhouse gas emissions (3.<del>1814</del>) and GHGgreenhouse gas removals

[SOURCE: ISO 14064-1:2018, 3.2.6]

3.<del>21</del>17

greenhouse gas source

**GHG** source

process (3.39) that releases a GHGgreenhouse gas (3.16) into the atmosphere

[SOURCE: ISO 14064-1:2018, 3.1.2]

3.2218

grid electricity grid

grid

electricity from the grid which is from the public electricity network

 $[SOURCE: ISO\ 52000-1:2017, 3.4.8 \textcolor{red}{--} \textcolor{blue}{modified}]$ 

3.<del>23</del>19

indirect greenhouse gas emissions emission

indirect GHG emission

<u>CHG greenhouse gas emission</u> (3.1814) that is a consequence of an <u>organization</u>'s (3.3527) operations and activities, but that arise from <u>greenhouse gas sources</u> (3.2117) that are not owned or controlled by the <u>organization</u> (3.35)

Note 1 to entry: These emissions occur generally in the upstream and/or downstream chain.

[SOURCE: ISO 14064-1:2018, 3.1.11]

#### 3.<del>24</del>20

# in -situ plasma cleaning

IPC

technique using the chemicalchemically reactive oxygen plasma to remove the hydrocarbon contaminants

# in -situ thermal cleaning

ITC

thermal cleaning is a combined process (3.39) involving of pyrolysis and oxidation

#### 3.2622

#### key performance indicator

**KPI** 

Type of measure of performance used by industry Note 1 to entry: KPIs are commonly used by an organization (3.35) to evaluate its success or the success of an activity in which it is engaged.

[SOURCE: ISO 19694-1:2021, 3.23]

# 3.27

level of assurance degree of confidence in the GHG (3.16) statement Teh Standards [SOURCE: ISO 14064-1:2018, 3.4.13] (https://standards.iteh.ai)

#### 3.28

# lower heat value

LHV

# net calorific value

**NCV** 

absolute value of the specific heat (enthalpy) of combustion, for unit mass of the fuel burned in oxygen at constant pressure under such conditions that all the water of the reaction products remains as water vapour (at 0,1 MPa), the other products being as for the gross calorific value, all at the reference temperature

Note 1 to entry: Also referred to as "net calorific value" (NCV).

[SOURCE: ISO 1928: $\frac{2009}{2020}$ , 3.1.3, modified - the term "net calorific value at constant volume" has been replaced with "lower heat value<del>" and Note 1 to entry", the admitted term "net calorific value"</del> has been added, and "(enthalpy)" has been added to the definition.]

### 3.<del>29</del>23

# mass balance

relationship between input and output quantity of a specific substance in a defined system, taking into account the formation or decomposition of that substance in the system

[SOURCE: ISO 19694-1:2021, 3.27]

# 3.30

microelectromechanical systems micro-electromechanical system

MEMS